

AMENDMENTS TO THE CLAIMS

LISTING OF CLAIMS

Claims 1-25 (canceled)

26. (previously presented) A method for fabricating a semiconductor component comprising:

providing a semiconductor die comprising an electrically insulating layer and a plurality of die contacts;

forming a first electrode on the electrically insulating layer in electrical communication with a first die contact;

forming a dielectric layer on the first electrode;

forming a second electrode on the dielectric layer in electrical communication with a second die contact;

forming a first terminal contact on the die in electrical communication with the first electrode;

forming a second terminal contact on the die in electrical communication with the second electrode; and

forming a protective layer on the die encapsulating the first electrode, the dielectric layer and the second electrode.

27. (previously presented) The method of claim 26 wherein the forming the first electrode step comprises patterning a first redistribution layer on the die.

28. (previously presented) The method of claim 26 wherein the forming the second electrode step comprises patterning a second redistribution layer on the die.

29. (previously presented) The method of claim 26 wherein the first die contact comprises a ground contact for the die.

30. (previously presented) The method of claim 26 wherein the second die contact comprises a power contact for the die.

31. (previously presented) The method of claim 26 wherein the die contacts comprise bond pads.

32. (previously presented) The method of claim 26 wherein the electrically insulating layer comprises a passivation layer.

33. (previously presented) The method of claim 26 wherein the terminal contacts comprise bumps or balls in a grid array.

34. (currently amended) A method for fabricating a semiconductor component with an on board capacitor comprising:

providing a semiconductor die comprising a plurality of die contacts;

forming a first redistribution layer on the die;

patterning the first redistribution layer to form a first electrode of the capacitor in electrical communication with a first die contact;

forming a dielectric layer of the capacitor on the first electrode;

forming a second redistribution layer on the die and on the dielectric layer; and

patterning the second redistribution layer to form a second electrode of the capacitor in electrical communication with a second die contact; and

forming at least one terminal contact on the die in electrical communication with either the first electrode or the second electrode.

35. (currently amended) ~~The method of claim 34~~
~~further comprising~~

A method for fabricating a semiconductor component with an on board capacitor comprising:

providing a semiconductor die comprising a plurality of die contacts;

forming a first redistribution layer on the die;

patternning the first redistribution layer to form a first electrode of the capacitor in electrical communication with a first die contact;

forming a dielectric layer of the capacitor on the first electrode;

forming a second redistribution layer on the die and on the dielectric layer;

patternning the second redistribution layer to form a second electrode of the capacitor in electrical communication with a second die contact; and

forming a first terminal contact on the die in electrical communication with the first electrode.

36. (currently amended) ~~The method of claim 34~~
~~further comprising~~

A method for fabricating a semiconductor component with an on board capacitor comprising:

providing a semiconductor die comprising a plurality of die contacts;

forming a first redistribution layer on the die;

patternning the first redistribution layer to form a first electrode of the capacitor in electrical communication with a first die contact;

forming a dielectric layer of the capacitor on the first electrode;

forming a second redistribution layer on the die and on the dielectric layer;

patterning the second redistribution layer to form a second electrode of the capacitor in electrical communication with a second die contact; and

forming a second terminal contact on the die in electrical communication with the second electrode.

37. (currently amended) The method of claim 34 36 further comprising forming a protective layer on the die encapsulating the first electrode, the dielectric layer and the second electrode.

38. (currently amended) The method of claim 34 36 wherein the first ~~die contact~~ comprises electrode is in electrical communication with a ground die contact and the second electrode is in electrical communication with ~~die contact~~ comprises a power die contact.

39. (previously presented) A method for fabricating a semiconductor component with an on board capacitor comprising:

providing a semiconductor die comprising a plurality of integrated circuits and a plurality of die contacts in electrical communication with the integrated circuits;

forming an on board capacitor on die by forming a first electrode on the die in electrical communication with a ground die contact, a dielectric layer on the first electrode, and a second electrode on the dielectric layer in electrical communication with a power die contact; and

forming a plurality of terminal contacts on the die in electrical communication with the die contacts, including a ground terminal contact in electrical communication with the first electrode, and a power terminal contact in electrical communication with the second electrode.

40. (previously presented) The method of claim 39 further comprising forming a protective layer on the die encapsulating the capacitor.

41. (previously presented) The method of claim 39 wherein the terminal contacts comprise bumps or balls in a grid array.

42. (previously presented) The method of claim 39 wherein forming the first electrode comprises patterning a first redistribution layer for the die.

43. (previously presented) The method of claim 39 wherein forming the second electrode comprises patterning a second redistribution layer for the die.

44. (previously presented) The method of claim 39 further comprising forming a ground conductor on the die in electrical communication with the ground die contact and the first electrode.

45. (previously presented) The method of claim 39 further comprising forming a plurality of conductors on the die in electrical communication with the die contacts and the terminal contacts comprising portions of a redistribution layer.

46. (previously presented) The method of claim 39 wherein the component comprises a package.

47. (previously presented) The method of claim 39 wherein the die is contained on a semiconductor wafer comprising a plurality of dice identical to the die.

48. (currently amended) A method for fabricating a semiconductor component with an on board capacitor comprising:

providing a semiconductor wafer containing a semiconductor die;

forming a first redistribution layer on the wafer;

~~forming a first portion of the first redistribution layer into a first electrode;~~

~~of the capacitor by patterning the first redistribution layer;~~

forming a dielectric layer on the first electrode;

forming a second redistribution layer on the wafer;

~~forming a second portion of the second redistribution layer into a second electrode on the dielectric layer;~~

~~by patterning the second redistribution layer; and~~

forming a protective layer on the wafer encapsulating the first electrode, the dielectric layer and the second electrode; and

forming at least one terminal contact on the die in electrical communication with either the first electrode or the second electrode.

49. (previously presented) The method of claim 48 further comprising singulating the die from the wafer.

50. (currently amended) ~~The method of claim 48 further comprising~~

A method for fabricating a semiconductor component with an on board capacitor comprising:

providing a semiconductor wafer containing a semiconductor die;

forming a first redistribution layer on the wafer;

forming a first electrode by patterning the first redistribution layer;

forming a dielectric layer on the first electrode;

forming a second redistribution layer on the wafer;

forming a second electrode on the dielectric layer by patterning the second redistribution layer;

forming a protective layer on the wafer encapsulating the first electrode, the dielectric layer and the second electrode; and

forming a plurality of terminal contacts on the die including a ground terminal contact in electrical communication with the first electrode and a power terminal contact in electrical communication with the second electrode.

Claims 51-59 (canceled)